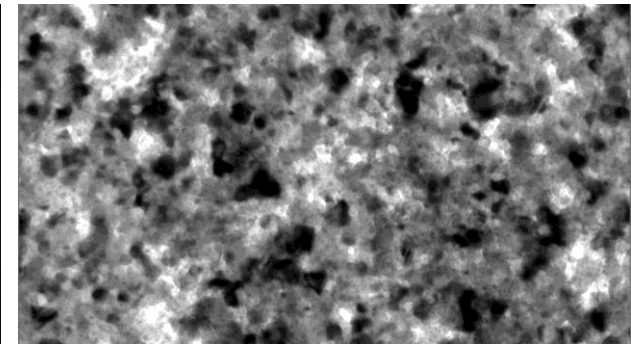
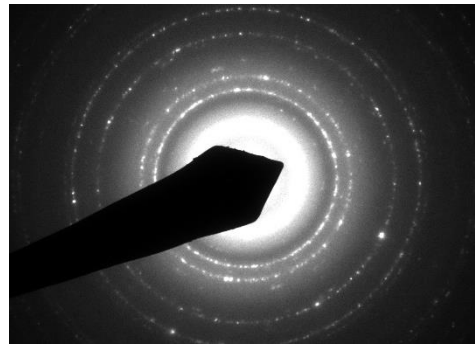


Exceptional service in the national interest



Nanodispersed Cu-Nb for enhanced radiation tolerance

Presented by:

Samuel A. Briggs

Co-authors: J. Ihlefeld¹, B. Muntifering, K. Hattar, P. Hosemann²

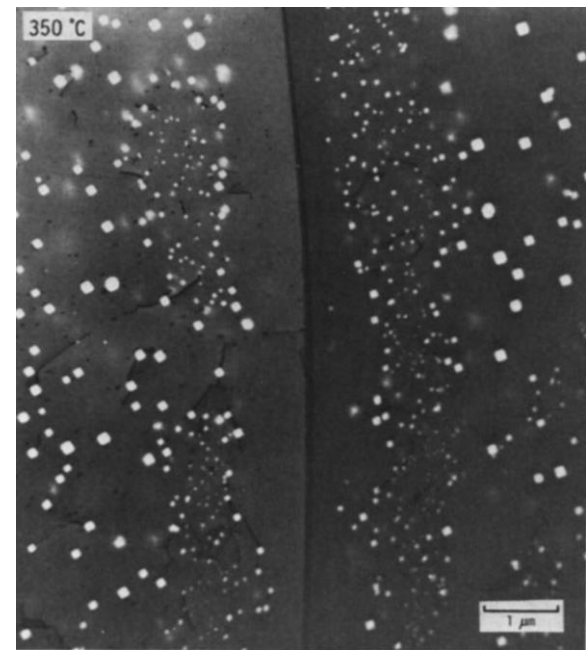
¹University of Virginia, ²University of California - Berkeley



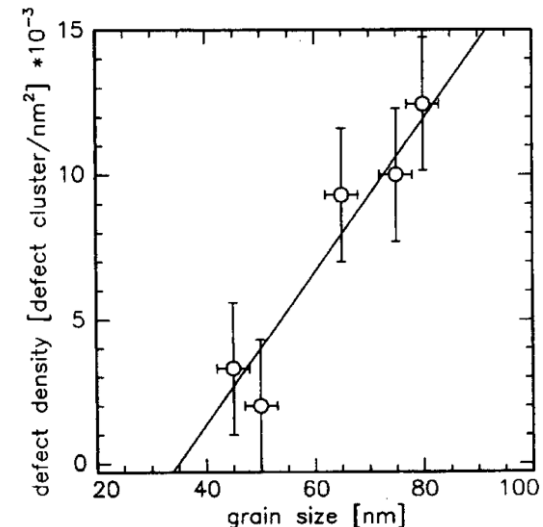
Sandia National Laboratories is a multimission laboratory managed and operated by National Technology and Engineering Solutions of Sandia, LLC, a wholly owned subsidiary of Honeywell International, Inc., for the U.S. Department of Energy's National Nuclear Security Administration under contract DE-NA0003525.

Motivation

- Nanostructured materials are of general interest to the nuclear materials community for improving radiation tolerance
 - High densities of features and interfaces serve as sinks for point defects resulting from radiation damage
- Cu-Nb serves as an idealized system for studying these systems
 - Cu (fcc) & Nb (bcc) are immiscible, allowing for study of ideal interfaces without potentially complex intermediate phases or chemical effects
- Most work to date has been performed on nanolayered Cu-Nb
 - Nanodispersed or nanograined Cu-Nb geometries are more relevant to real systems (ODS, UFG)



Void-denuded zone in Cu
(Neutron-irradiated, 350 °C)

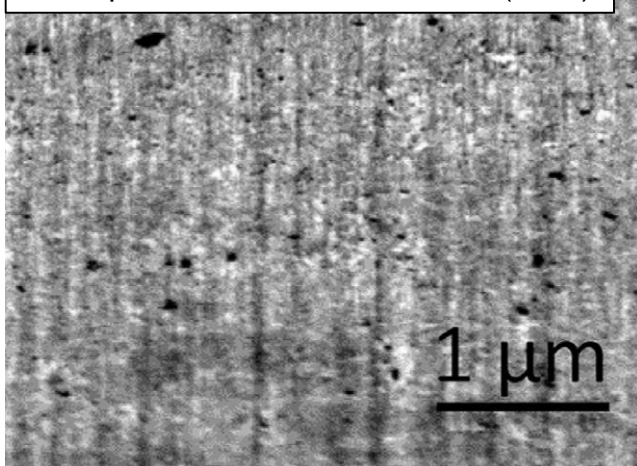


Defect densities vs. grain size in irradiated Pd
(240 keV Kr, 2E16 ions/cm²)

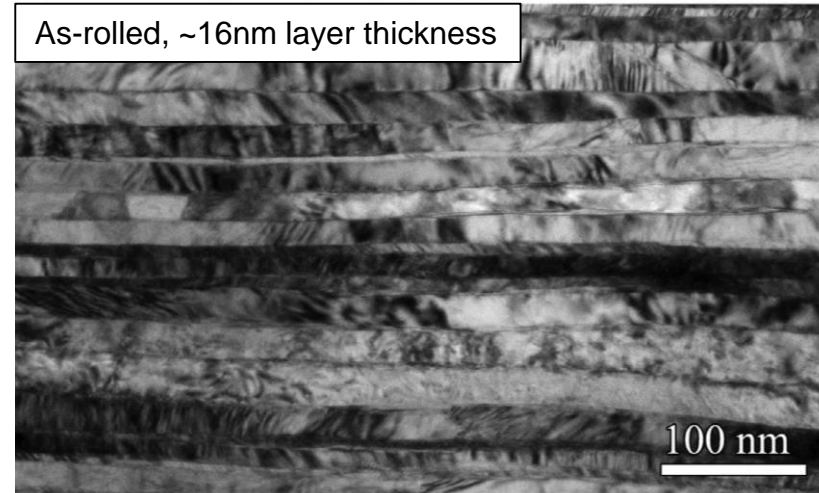
Previous studies of radiation tolerance in Cu-Nb

- Many studies of radiation damage and He implantation in Cu-Nb nanolaminates
 - Usually produced by accumulated roll-bonding (bulk) or alternating deposition (thin films)
 - Have demonstrated He bubble growth is arrested by these interfaces
- Averbach group @ UIUC has had success preparing nanodispersed Cu-Nb specimens via HPT and has shown phase separation under irradiation, but little is reported on the resulting radiation tolerance

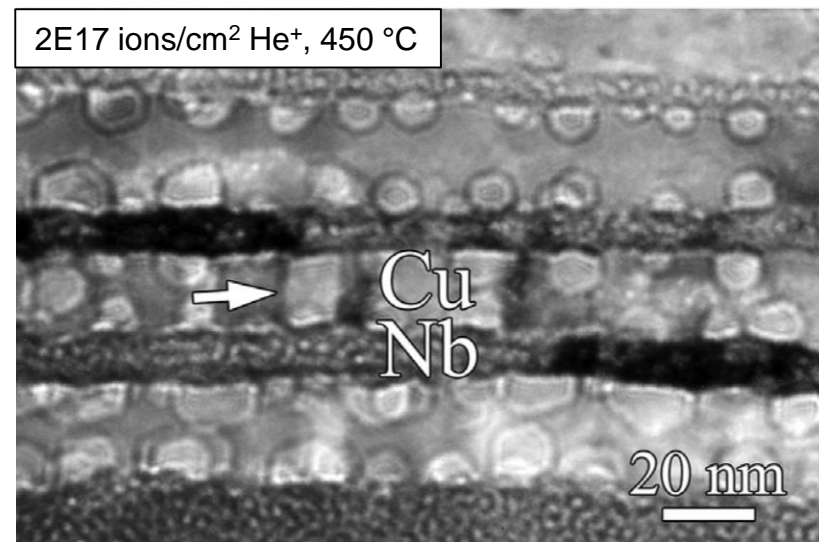
As-deposited Cu-10Nb after HPT (SEM)



As-rolled, ~16nm layer thickness



$2\text{E}17$ ions/ cm^2 He $^+$, 450 $^{\circ}\text{C}$

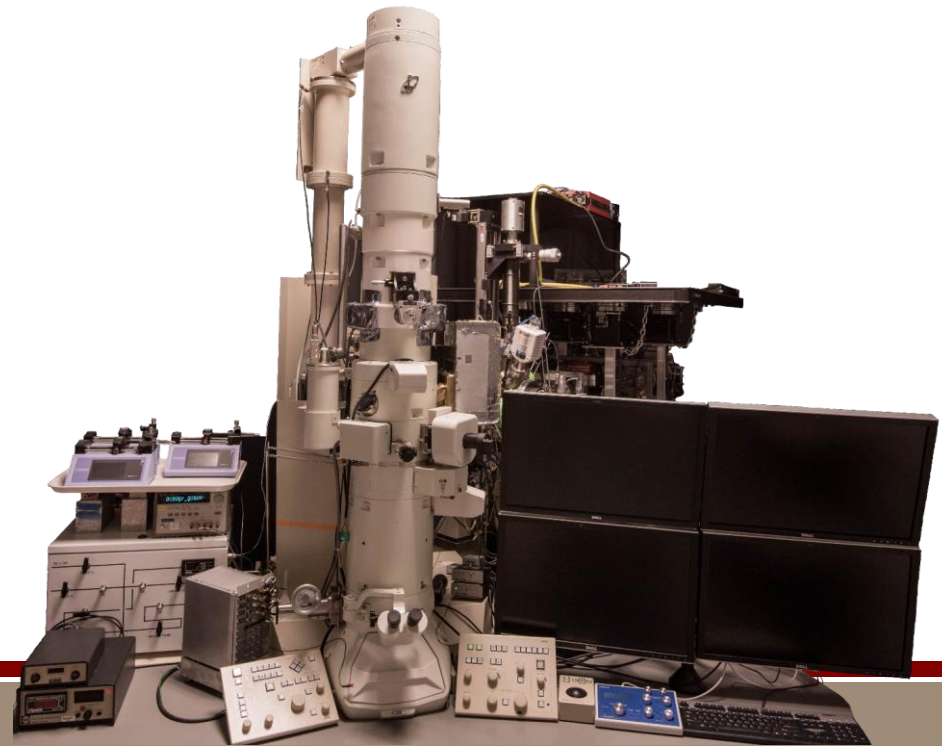
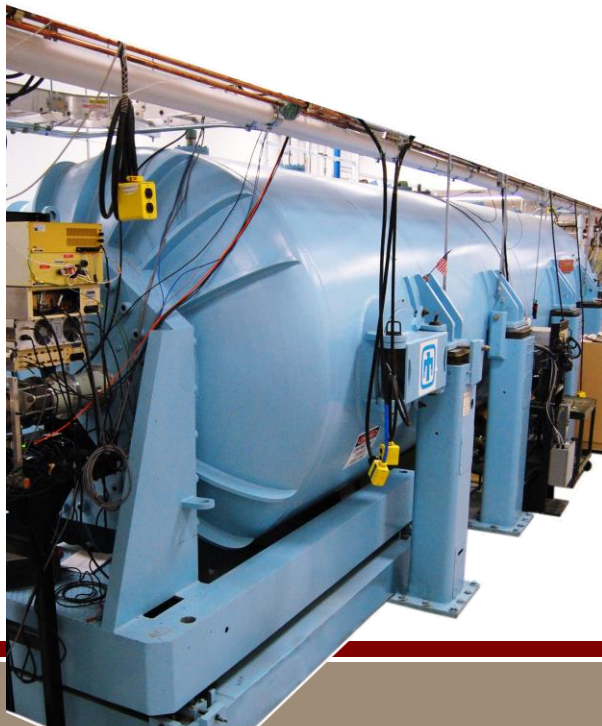


Experimental Goals

- Generate nanodispersed Cu-Nb thin films with varied compositions
 - Characterize and optimize microstructures for a given condition
- Irradiate films with heavy ions and characterize damage microstructures
- Implant films with He and characterize resulting bubble microstructures

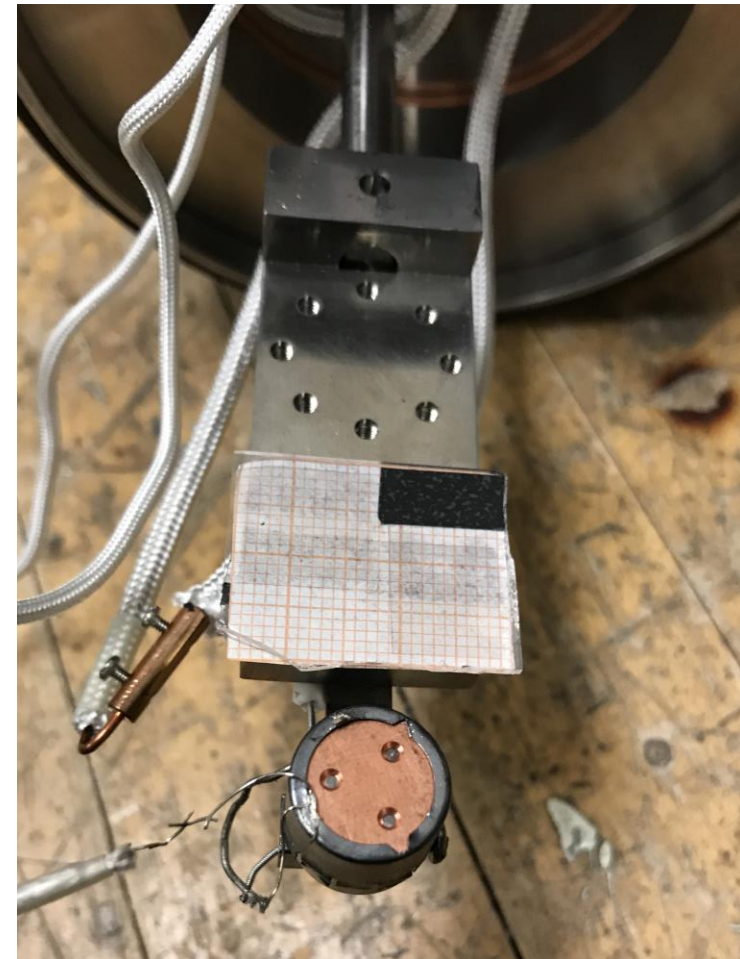
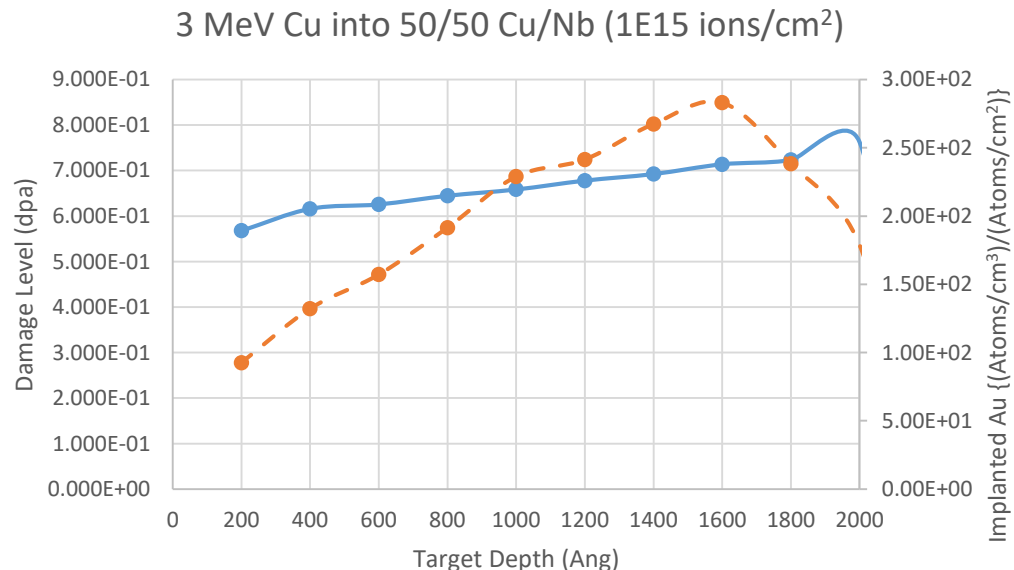
Experimental

- Cu-Nb thin films with various atomic ratios have been created through magnetron sputtering at RT
 - Either single crystal NaCl or Si_3N_4 window grid substrates
- As-deposited films were either vacuum annealed or irradiated at temperature to encourage recrystallization
 - 500 °C anneal, or 3 MeV Cu^{++} to 1 dpa @ 350 or 500 °C



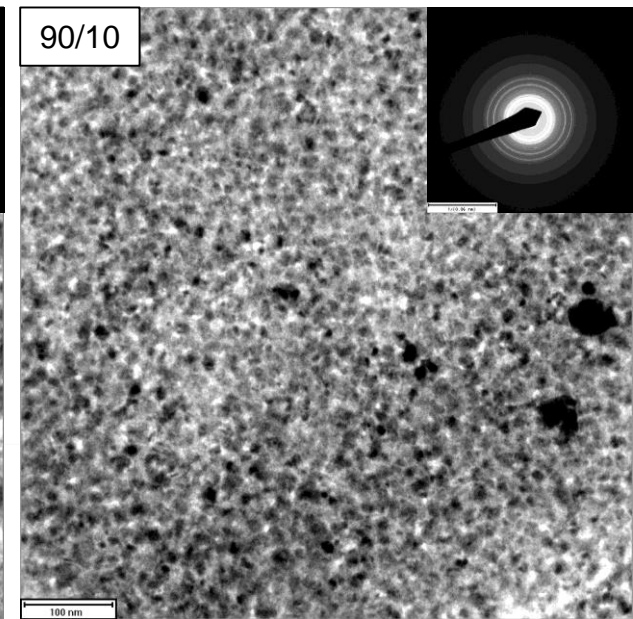
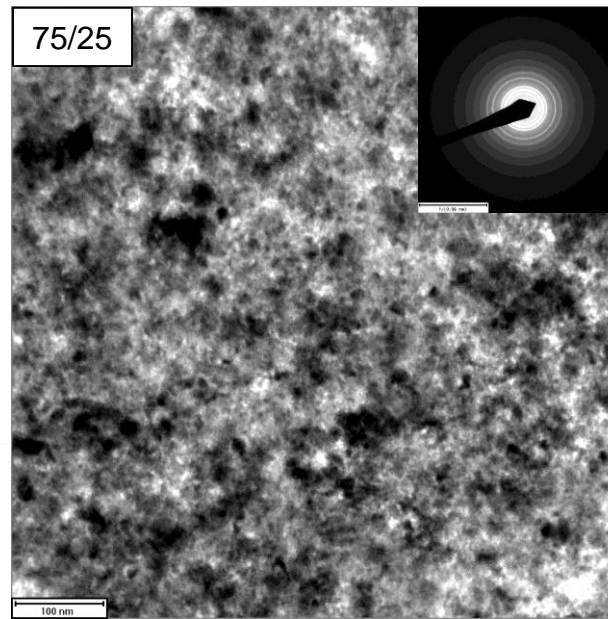
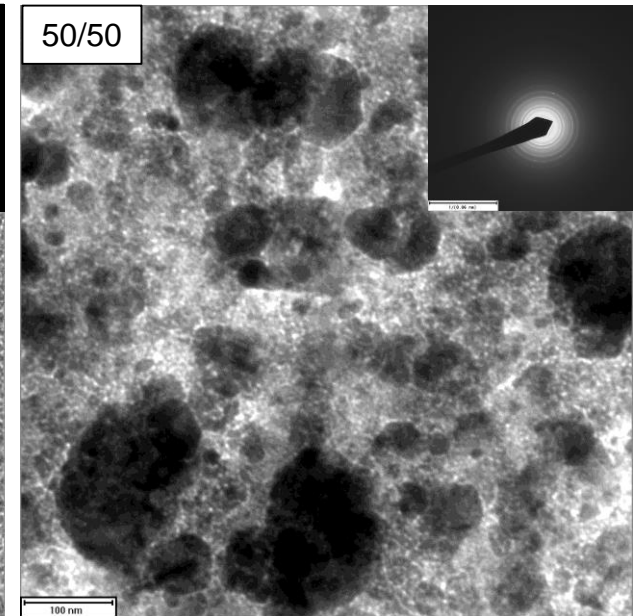
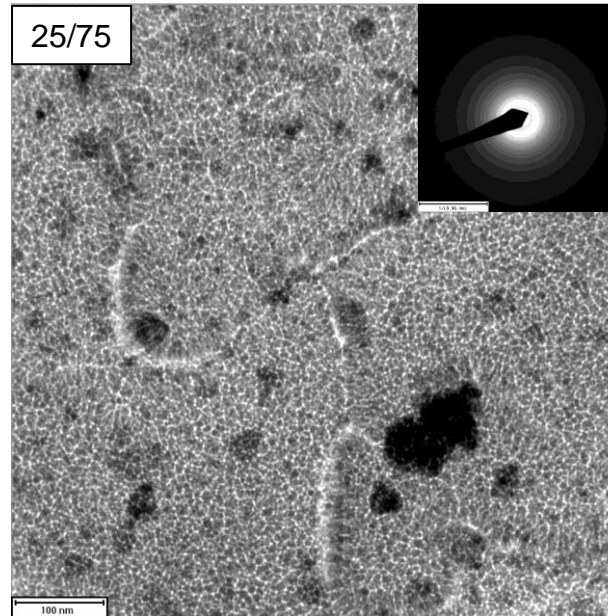
Ion Irradiation Calculation

- SRIM was used to calculate damage in specimens
 - $1.61\text{E}15$ ions/cm² per dpa
- Specimen temperature was maintained using LabView-controlled button heater

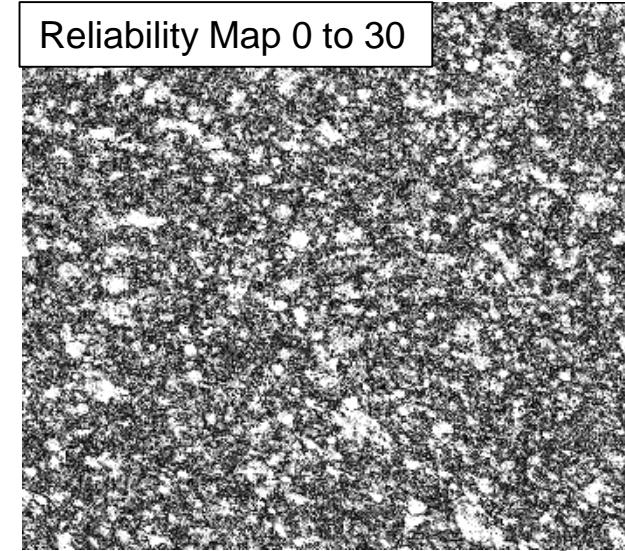
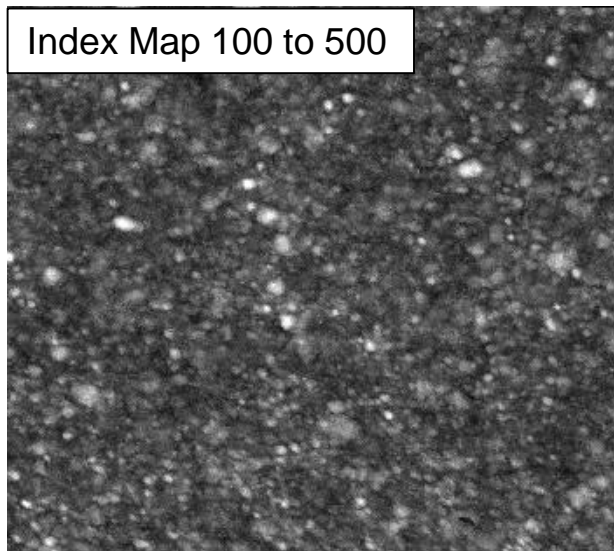
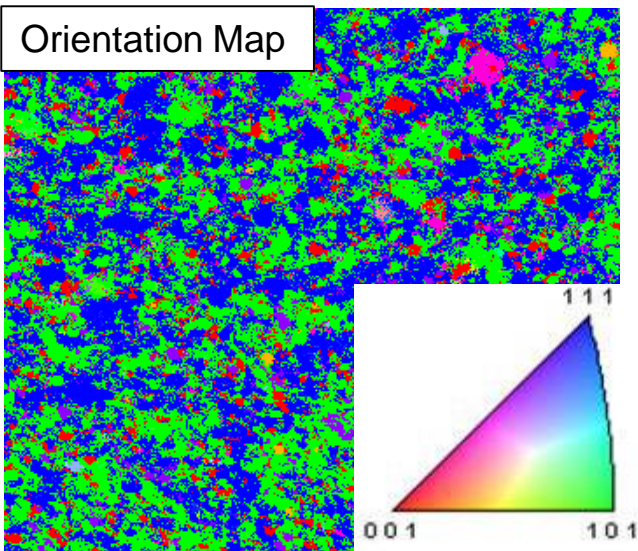
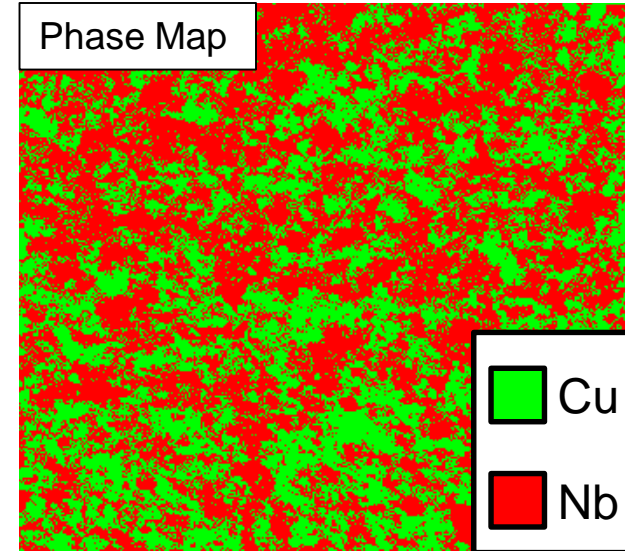
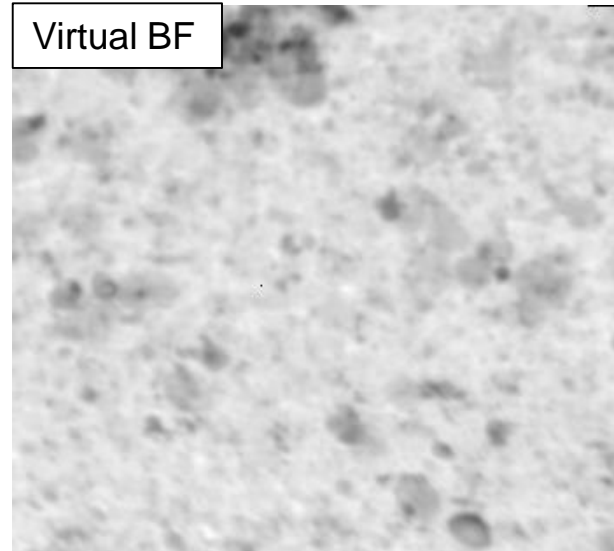
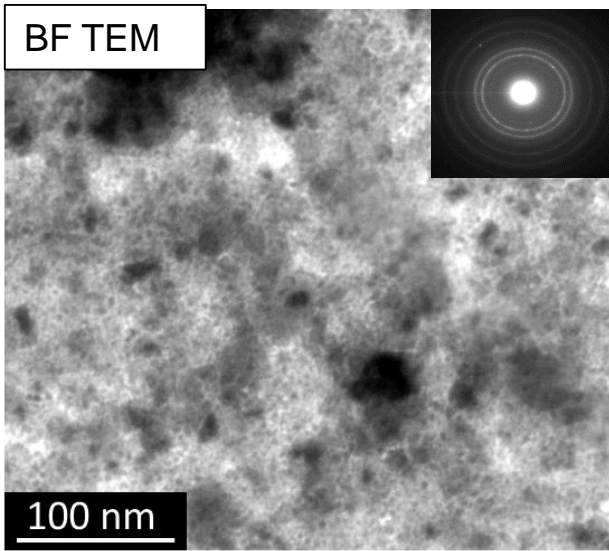


As-deposited Microstructures

- Microstructures appear porous
- Increasing crystallinity with increasing Cu content

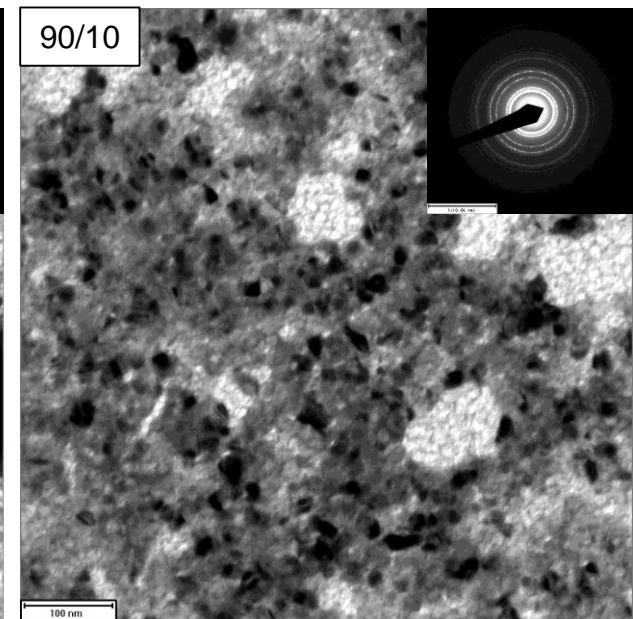
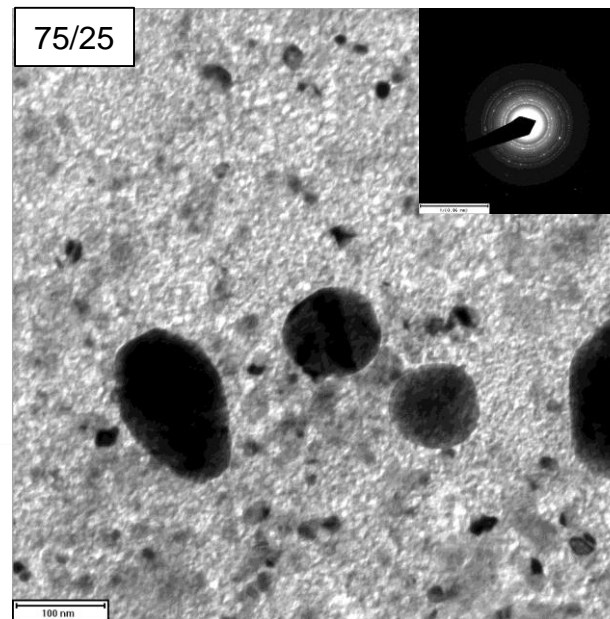
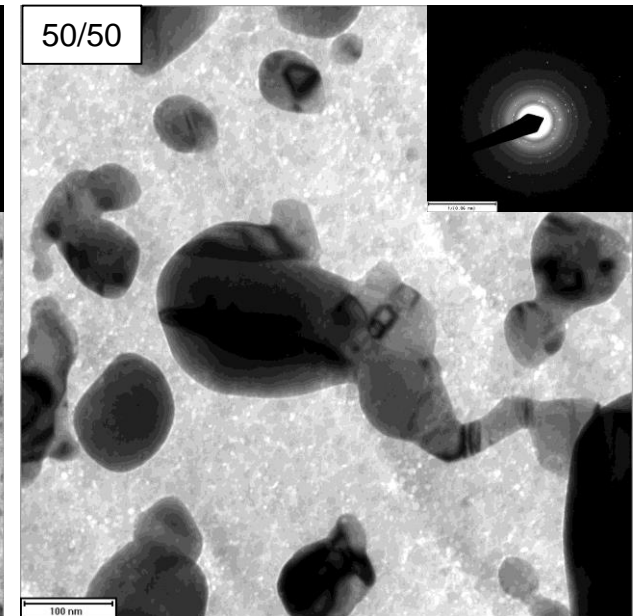
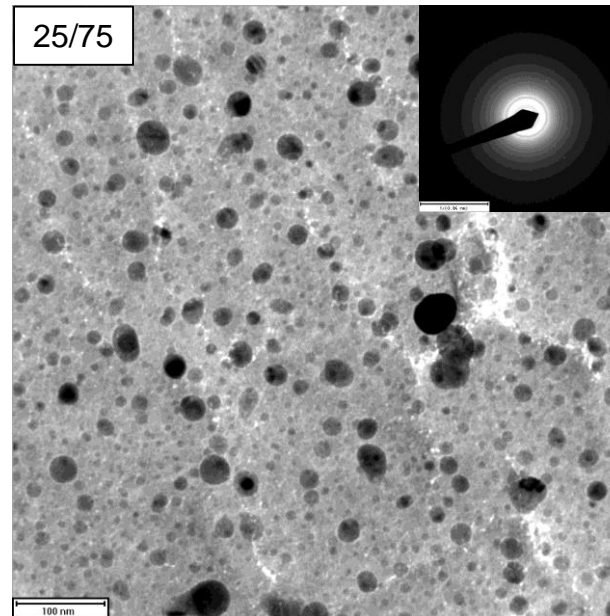


PED of As-Deposited Cu-10Nb



Annealed Microstructures (1hr, 500 °C)

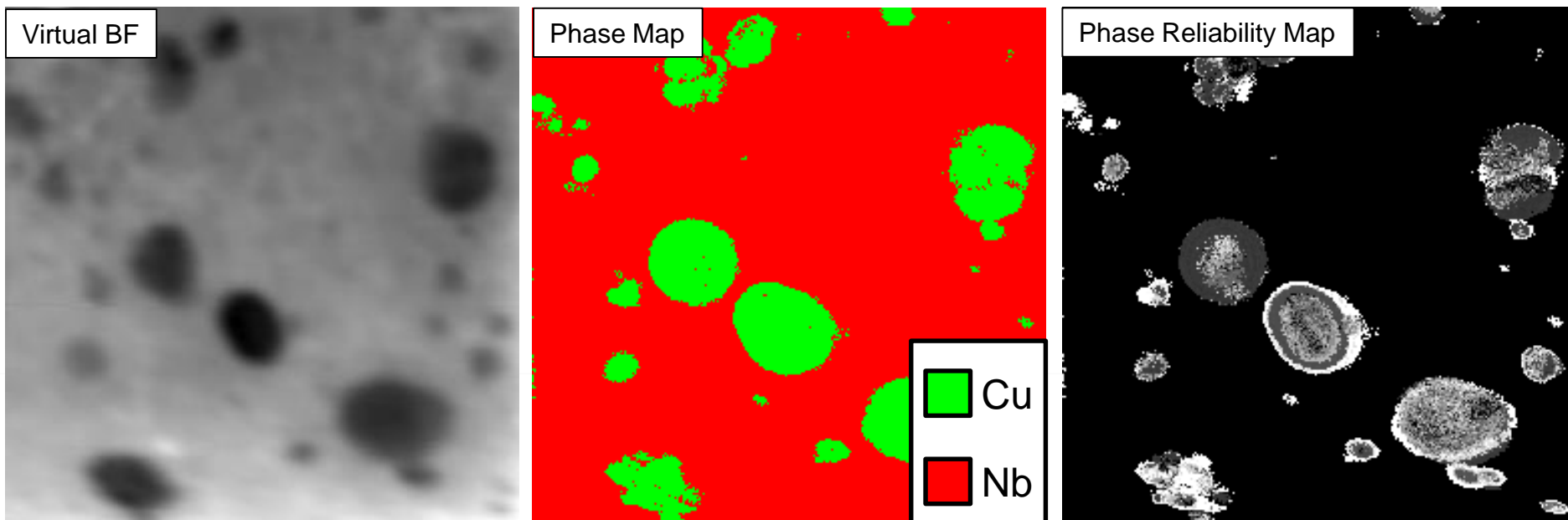
- Annealing results in Cu islands on a mostly amorphous Nb substrate
- Size of islands varies dramatically with composition
- Porosity is prevalent on Nb “substrates”



PED of Annealed Microstructures

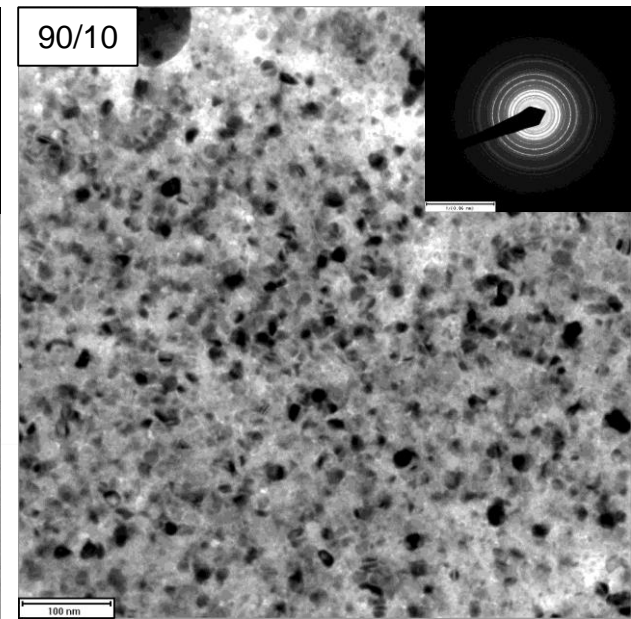
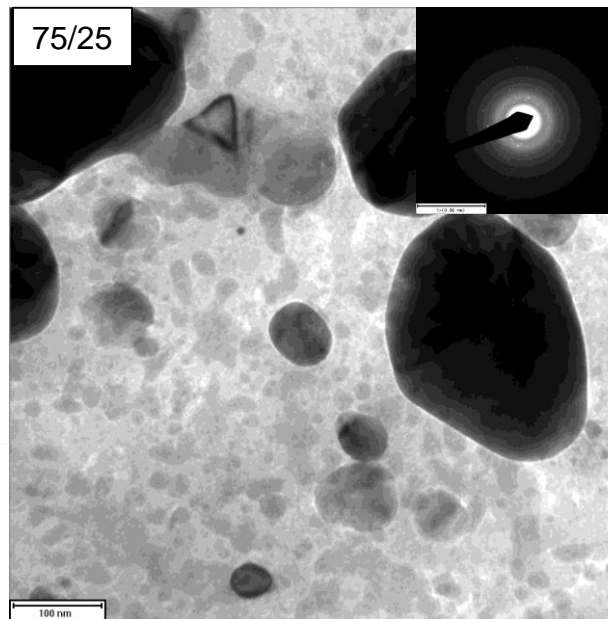
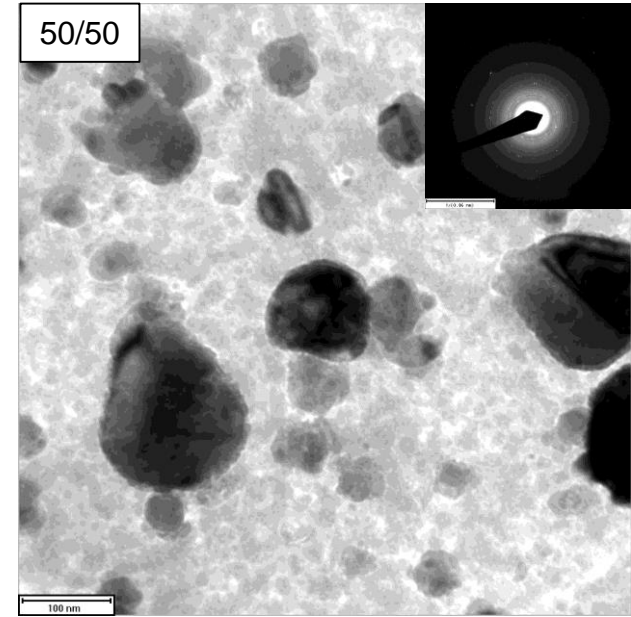
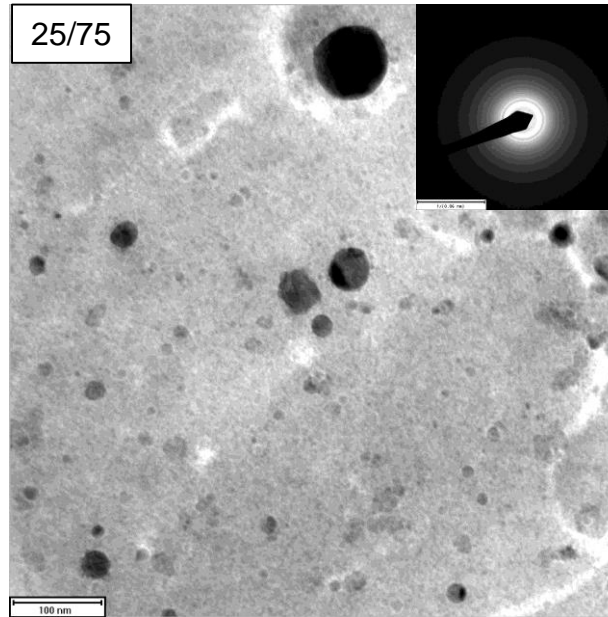
- PED of annealed specimen confirms that dark contrast is a Cu phase.
- Most patterns corresponding to Nb phase actually appear amorphous.

25/75 Cu/Nb on NaCl
Annealed, 500 °C, 1 hr



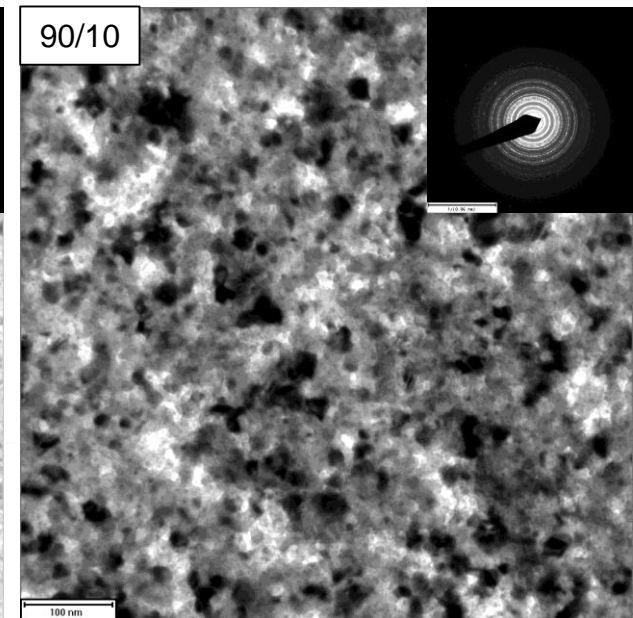
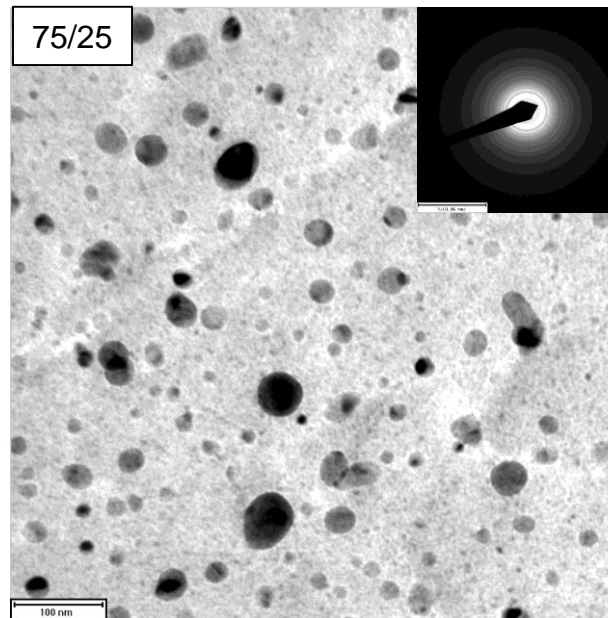
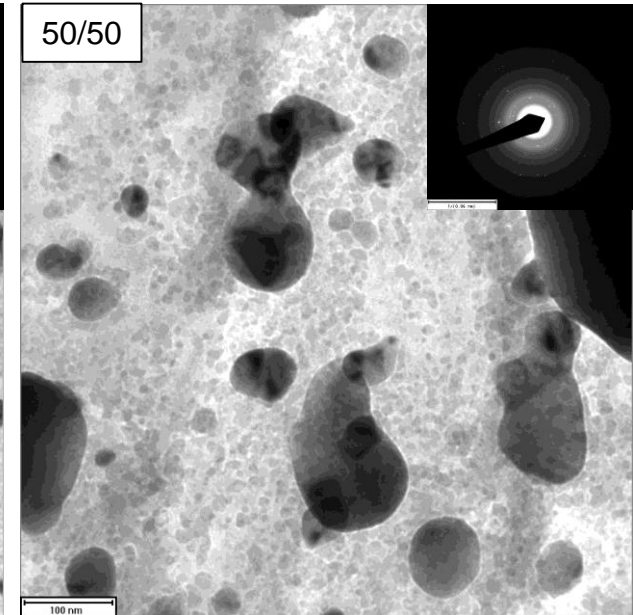
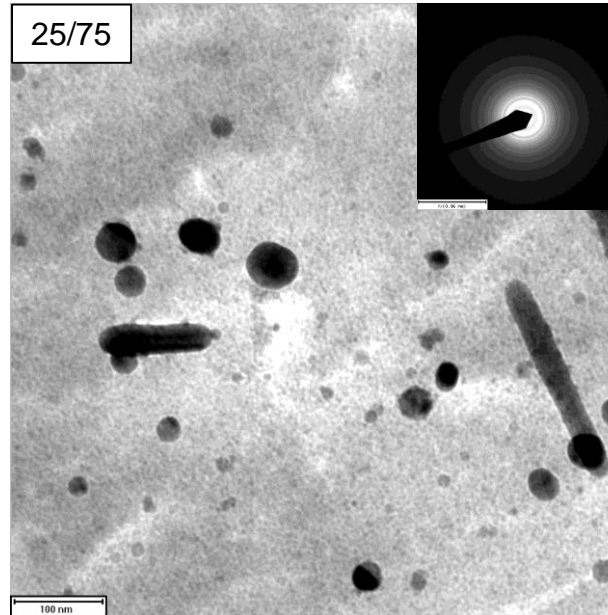
Irradiated Microstructures (1 dpa, 350 °C)

- Irradiation at a lower temperature yields similar structures to higher temperature anneal



Irradiated Microstructures (1 dpa, 500 °C)

- Irradiation at a higher temperature results in more uniformly sized Cu islands (90/10 exception)
- Still not enough to recrystallize Nb

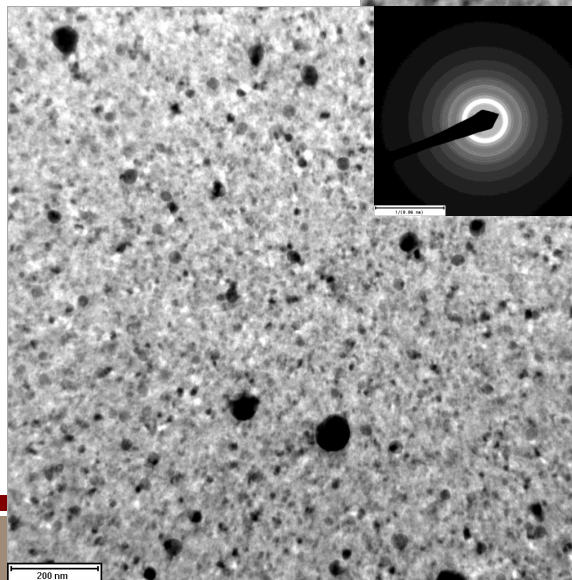
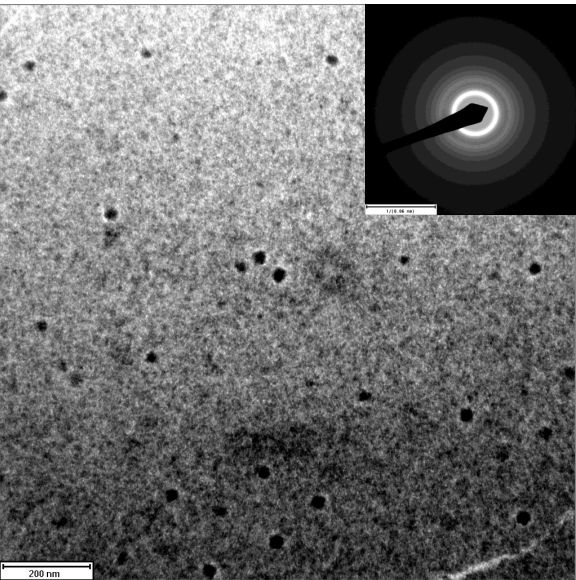
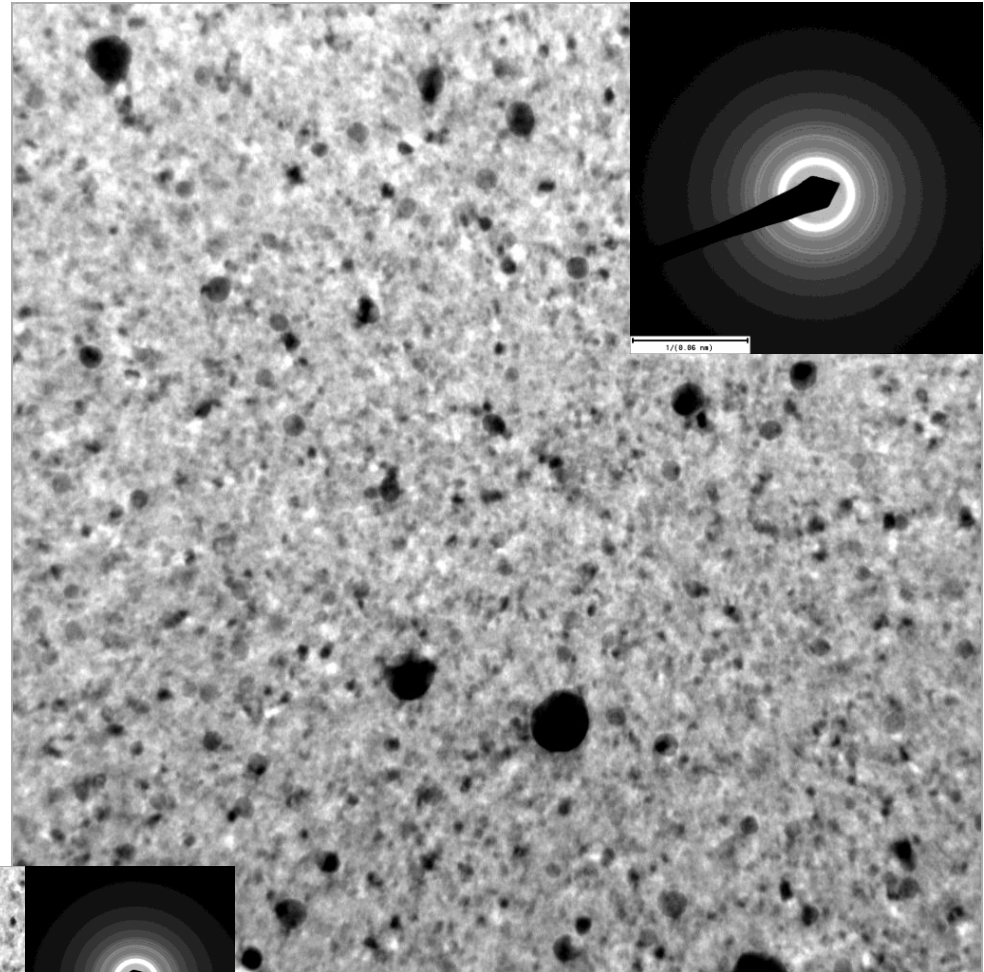


Discussion

- Due to drastically different melting temperatures and thin-film geometries, Cu appears to be “wetting” to the surface and organizing into individual precipitates/crystals
- Nb substrate remains immobile and amorphous, but contains nanometer-sized pores
 - Smaller than those seen using de-alloying, may still be of use to study nanofeatured materials for radiation tolerance
- This effect not previously observed in nanolayered materials – may be due to higher stresses in co-deposited films
- Open to other hypotheses...

In-Situ Anneal

- 50/50 Cu/Nb on Si_3N_4 grid
- Ramp rate of 30 °C/min (14 mins)
- Held at 450 °C for 10 mins
- Smaller Cu phase precipitates observed to start growth at ~120 °C
- Handful of precipitates begin to coarsen at ~200 °C
- Small grains begin to recrystallize with continued annealing at 450 °C



Next Steps

- Further in-situ annealing & irradiation may help elucidate mechanism of microstructural evolution
- Pursue bulk sample preparation via cryo-ball milling
 - May be able to avoid surface wetting effect by using bulk materials
- He bubble distribution following implantation still of interest
- Eventual neutron irradiations in ACRR planned

Summary & Conclusions

- Microstructural optimization of various co-deposited Cu/Nb films was attempted using annealing and irradiation treatments (up to 500 °C)
- Cu was observed to wet and coalesce on the film surface while Nb remained immobile became porous
- Observed behavior, previously unobserved in nanolayered materials, is likely due to high stresses inherent in co-deposited materials
- Future efforts are pursuing cryo-ball milling to avoid these surface effects

Acknowledgements

- Special thanks to Guild Copeland, Dan Buller, and Remi Dingreville.
- Sandia National Laboratories is a multi-mission laboratory managed and operated by National Technology & Engineering Solutions of Sandia, LLC., a wholly owned subsidiary of Honeywell International, Inc., for the U.S. Department of Energy's National Nuclear Security Administration under contract DE-NA0003525.



**Sandia
National
Laboratories**

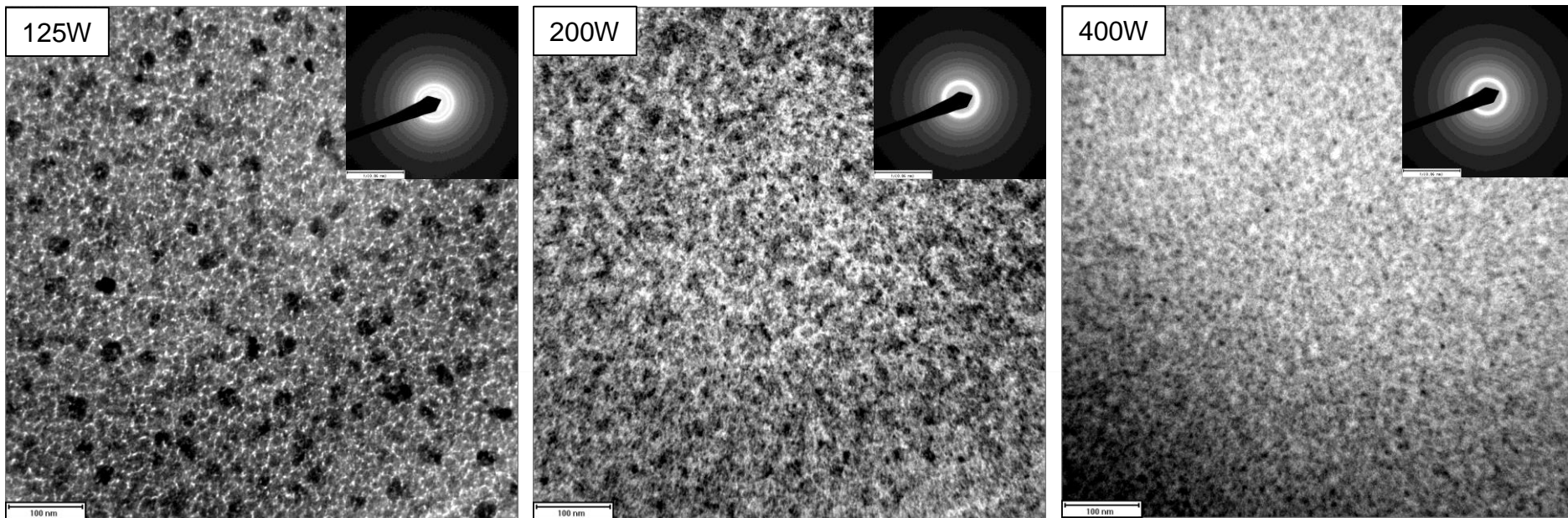


Berkeley
UNIVERSITY OF CALIFORNIA

Thank you for your attention.
Questions?

As-Deposited Microstructures

- Deposited on silicon nitride TEM windows
- Cu/Nb contents listed



Irradiated Microstructures (1 dpa, 500 °C)

- Deposited on silicon nitride TEM windows
- Cu/Nb contents listed

